CONSIDERED: /P.T.R./ EFS-Web Receipt date: 08/16/2006

Docket No.: SHIGA7.054APC

10589681 - GAU: 1795

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with

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August 16, 2006

(Date)

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## CONSIDERED: /PIAPS Rec'd PCT/PTO 16 AUG 2006

Applicant Ogata et al.

App. No

Unknown

Filed

Herewith

For

POLYMER COMPOUND,

PHOTORESIST COMPOSITION INCLUDING THE POLYMER COMPOUND, AND RESIST

PATTERN FORMATION METHOD

Examiner

Unassigned

Art Unit Unknown

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 references to be considered by the Examiner. Also enclosed are 3 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

INFORMATION DISCLOSURE STATEMENT

This Information Disclosure Statement is being filed within three months of the filing date, with an RCE or before receipt of a first office action after an RCE and no fee is required.

The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: August 16, 2006

Neil S. Bartfeld, Ph.D. Registration No. 39,901

Agent of Record Customer No. 20,995 (619) 235-8550

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		PTO/SB/08 Equivalent
	Application No.	Unknown 10/589681
INFORMATION DISCLOSURE	Filing Date	Herewith 10/589681
STATEMENT BY APPLICANT	First Named Inventor	Toshiyuki Ogata
	Art Unit	thiknown 1795
(Multiple sheets used when necessary)	Examiner	Unassigned Ponder Thompson-Rummel
SHEET 1 OF 1	Attorney Docket No.	SHIGA7.054APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
/P.T.R./	1	2002/0177068 A1	11-28-2002	Park et al.	
/P.T.R./	2	6,329,125 B2	12-11-2001	Takechi et al.	

[	FOREIGN PATENT DOCUMENTS					
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T <sup>1</sup>

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T¹
/P.T.R./	3	Hagiwara et al. "Characterization of Fluoropolymer Resist for 157-nm Lithography." Journal of Photopolymer Science and Technology. 16(4):557-564 (2003).	
/P.T.R./	4	Houlihan et al. "New Flourinated Resins for 167nm Lithography Application." Journal of Photopolymer Science and Technology. 16(4):581-590 (2003).	
/P.T.R./	5	Kawaguchi et al. "Dry-Etching Resistance for Fluoropolymers for 157-nm Single-Layer Resists." Proceedings of SPIE. 5039:43-52 (2003).	

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Examiner: Signature /Ponder Thompson Rummel/ Date Considered 06/18/2008

\*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to a pplicant.